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PATENT
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THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants	Wolfgang Dettman, <i>et al.</i>
Application No. 10/667,552	Filing Date: September 22, 2003
Title of Application:	Photomask, In Particular Alternating Phase Shift Mask, With Compensation Structure
Confirmation No. 9996	Art Unit: 2836
Examiner	

Commissioner for Patents
Post Office Box 1450
Alexandria, VA 22313-1450

Information Disclosure Statement by Applicants

As a means of complying with the duty of disclosure set forth in 37 CFR §1.56, Applicants list the following references (copies of the listed patents and papers enclosed).



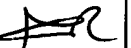
U.S. Patent Documents				
Exam. Initials	Class/ Subclass.	Document No.	Date	Name
	438/691	6,103,626	August 15, 2000	Kim

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May 12, 2005

Rhonda S. Esaw

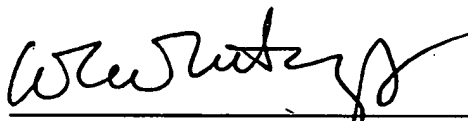
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Foreign Patent Documents			
Exam. Initials	Document No.	Date	Country
	DE 3703582 C1	April 7, 1988	Germany w/English abstract
	DE 19632845 A1	October 16, 1997	Germany w/English abstract
	EP 0993030 A2	April 12, 2000	Europe

The listed patents pertain in a general way to the subject matter of the application, but are not necessarily considered to be analogous prior art.

Respectfully submitted,

May 12, 2005



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8/2/05
Date Considered


Examiner